





Moving Single-Event Mechanism Testing and Analysis into the Time-Domain

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Sandia is a multiprogram laboratory operated by the Sandia Corporation, a Lockheed Martin Company, for the United States Department of Energy under contract DE-AC04-94AL85000.

Preview

- Time-dependent vs time-independent methods
 - Conflict between experiment and simulation
 - Benefits to time-domain techniques



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Preview

- Time-dependent vs time-independent methods
 - Conflict between experiment and simulation
 - Benefits to time-domain techniques
- Previous progress and present status
 - Purchase of high-speed measurement equipment
 - Development of high-speed packaging
 - Initial measurement of radiation-induced transients



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- Time-dependent vs time-independent methods
 - Conflict between experiment and simulation
 - Benefits to time-domain techniques
- Previous progress and present status
 - Purchase of high-speed measurement equipment
 - Development of high-speed packaging
 - Initial measurement of radiation-induced transients
- Proposed projects
 - Calibrate TCAD in the time-domain (IBM CMOS, IBM BiCMOS, TI CMOS, Jazz CMOS, Jazz BiCMOS)
 - Measure strained silicon transients (U Florida, MURI)



Time-Independent Measurements



Standard Heavy Ion Microbeam and Laser Methods



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Time-Independent Measurements



Issues with Time-Independendent Methods

- Limited TCAD calibration
- Limited operational configurations

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- Lack of transient information
- Experimental complexity

J. A. Pellish, et al., "Substrate engineering concepts to mitigate charge collection in deep trench isolation technologies," *IEEE Trans. Nucl. Sci.*, vol. 53, pp. 3298-3305, Dec. 2006.



SCHOOL OF ENGINEERING

Time-Dependent Simulations



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Serial Data At the Speed of Radiation



R. Krithivasan, et al., "An SEU hardening approach for high-speed SiGe HBT digital logic," IEEE Trans. Nucl. Sci., vol. 50, pp. 2126-2134, Dec. 2003.

<u>CMOS and BiCMOS</u> circuits now operate with time constants equal to or less than those of radiation-induced transients. <u>BURST ERRORS</u>



Solution

• Need a predictive tool for burst error rates



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- Use mixed-mode TCAD (Synopsys, CFDRC)



Solution

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- Need a predictive tool for burst error rates
- Use mixed-mode TCAD (Synopsys, CFDRC)
- Need to calibrate TCAD to experimental time-domain data



Vanderbilt Measurement System





Tektronix TDS6124C 12 GHz, 40 GS/s

59L 554. 50 GHz



Gore 2.92 mm RF coax 40 GHz

AFOSR DURIP Award

RF probe station (DC - 40 GHz)





High-Speed Package Development





Developed in collaboration with D. McMorrow (NRL)

- Works for SPA and TPA laser testing and microbeam too
- Close attention paid to impedance matching
 - All 50 Ω to ground
- Microstrips and 2.92 mm connectors 40 GHz
- Uses 1 mm² DUT tile



Typical Experimental Setup





Laser-Induced Transients with SiGe HBTs



High-resolution: 25 ps/point Long record lengths: 5000 points No ringing and no detectable low-pass filter effects

Planned publication in EDL



Future Work

- Ph.D. Focus
 - Use experimental transient measurements to calibrate TCAD and MRED
 - Burst error rates and frequency-dependent $\sigma_{\rm SEU}$
 - CMOS and BiCMOS
 - Targeting fall 2008 completion
- Primary experiments
 - Laser transient generation (NRL and VU FEL)
 - TI, IBM, and possibly Jazz
 - Prove measurement system at Sandia microbeam
 - Vacuum chamber, custom RF feedthrough



Future Work

- RHESE/ETDP leverage through Georgia Tech
 - CRYO-2 substrate tap splits
 - N. Pate (Q_{total}) SNL January 2008
 - J. Pellish (transient measurements)
 - CRYO-3a hardware (January 2008)
- U. Florida strained silicon; MURI leverage
 - Completed proof-of-concept 09/Nov/2007
- TI SET macro for scaling study
 - Down to 45 nm CMOS

